

Notice of References Cited	Application/Control No. 10/731,088	Applicant(s)/Patent Under Reexamination KAMIJIMA, AKIFUMI	
	Examiner Patricia A. George	Art Unit 1765	Page 1 of 1

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	C	US-6,916,597	07-2005	Kamijima et al.	430/314
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*	U	Abstract of Study for the design of high resolution novolak-DNQ photoresists: the effects of low-molecular-weight phenolic compounds on resist systems; Miyamoto et al.; July 1995; SPIE Vol. 2438, p. 223-234, Advances in Resist Technology and Processing XI
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.